



5/7/02
H7/Response
Patent
Attorney's Docket No. 027260-295

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION
METHOD OF PHOTOMASK, AND
FABRICATION METHOD OF
SEMICONDUCTOR INTEGRATED
CIRCUIT

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) Group Art Unit: 1756
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) Examiner: S. Mohamedulla
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RESPONSE UNDER 37 C.F.R. §1.116

Assistant Commissioner for Patents
Washington, D.C. 20231

Date: May 3, 2002

Sir:

This response responds to the Office Action dated January 3, 2002 (Paper No. 16).

Concurrently attached to this response is a Petition for Extension of Time for one month extension and copies of three references.

REMARKS

This response responds to the Office Action dated January 3, 2002 in which the Examiner rejected claims 7-8 and 22-23 under 35 U.S.C. § 112, first paragraph, rejected claims 7, 22, 23 and 28 under 35 U.S.C. § 102(b), rejected claims 2, 5, 7, 9-11, 14, 15, 17-23 and 28 under 35 U.S.C. § 102(e) and rejected claims 1-6, 8-21, 24 and 27 under 35 U.S.C. § 103.

Applicant respectfully traverses the Examiner's rejection of claims 7-8 and 22-23 under 35 U.S.C. § 112, first paragraph. Applicant respectfully points out to the Examiner,

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